## Are All Bifacial High-Efficiency c-Si Technologies Equally Sensitive to Potential-Induced Degradation?

**:: CSEM** 

Olatz Arriaga Arruti<sup>1,2</sup>, Alessandro Virtuani<sup>1,2</sup>, Bénédicte Bonnet-Eymard<sup>2</sup>, Matthieu Despeisse<sup>2</sup>, Christophe Ballif<sup>1,2</sup>

<sup>1</sup>Ecole Polytechnique Fédérale de Lausanne (EPFL), PV-Lab, Rue de la Maladière 71b, 2000 Neuchâtel, Switzerland <sup>2</sup>Swiss Center for Electronics and Microtechnology (CSEM), Sustainable Energy Center, Rue Jaquet Droz 1, 2000 Neuchâtel, Switzerland



- Bifacial high-efficiency technologies can be very sensitive to PID [1] Gnocchi et al., Cell Rep., 2024 when encapsulated in G/G module configurations. [2] Arriaga Arruti et al., Prog. Photovolt.: Res. Appl., PERC technology shows highest degradation under negative 2024 PID, while SHJ the lowest.
  - Degradation mechanisms and kinetics vary from cell to cell.
  - Solutions to mitigate PID should be studied on a case-to-case basis and tailored to every technology.
- This work was supported by the H2020 GOPV project that has received funding from the European Union's Horizon 2020 research and innovation programme under grant agreement No 792059.

PFI

PV-lab **IEM NEUCHATEL**